Docket No.: 5916/FET/FET/DV

# IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of :

Young Joseph PAIK :

Serial No. 09/998,384 : Group Art Unit: 2812

Filed: November 30, 2001 : Examiner:

For: FEEDFORWARD AND FEEDBACK CONTROL FOR CONDITIONING OF
CHEMICAL MECHANICAL POLISHING PAD
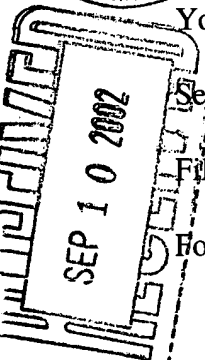
## INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
Washington, D.C. 20231

Sir:

In accordance with the provisions of 37 C.F.R. 1.56, 1.97 and 1.98, the attention of the

Patent and Trademark Office is hereby directed to the documents listed on the attached form

PTO-1449. It is respectfully requested that the documents be expressly considered during the

prosecution of this application, and that the documents be made of record therein and appear

among the "References Cited" on any patent to issue therefrom.
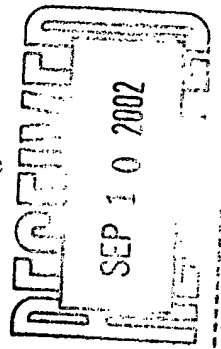
This Information Disclosure Statement is being filed within three months of the U.S.

filing date OR before the mailing date of a first Office Action on the merits. No certification or

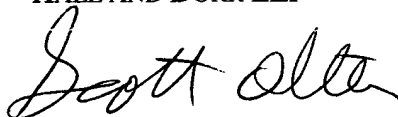fee is required.

This submission does not constitute a representation that a search has been made or that

no better art exists and does not constitute an admission or representation that any of the listed

documents is material or constitutes prior art. If it should be determined that any of the listed

documents does not constitute prior art under the United States law, Applicants reserve the right

to present to the Office the relevant facts and law regarding the appropriate status of such

document.

No certification or fee is believed to be required. However, the Commissioner is hereby

authorized to charge any additional fees should any be required for this submission, or credit any

overpayment to deposit account no. 08-0219.

Respectfully submitted,

HALE AND DORR LLP

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Date: 7/31/02

| INFORMATION DISCLOSURE CITATION IN AN APPLICATION<br><br>(PTO-1449) | ATTY. DOCKET NO.<br>5916/FET/FET/DV | SERIAL NO.<br>09/998,384 |
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| | APPLICANT<br>Young Joseph PAIK | |
| | FILING DATE<br>November 30, 2001 | GROUP<br>2812 |

*[OIPE stamp: JUL 3 1 2002 PATENT & TRADEMARK OFFICE]*

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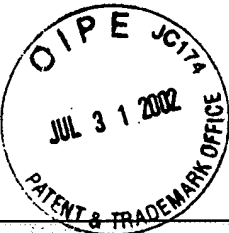| EXAMINER | DATE CONSIDERED |
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<table>
<tr><td rowspan="4"><strong>INFORMATION DISCLOSURE CITATION IN AN APPLICATION (PTO-1449)</strong></td><td><strong>ATTY. DOCKET NO.</strong><br>5916/FET/FET/DV</td><td><strong>SERIAL NO.</strong><br>09/998,384</td></tr>
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| | 09/656,031 | 09/06/00 | Chi et al. | Dispatching Component for Associating Manufacturing Facility Service Requestors with Service Providers | | |

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